L Number	Hits	Search Text	DB	Time stamp
1	3467	etch\$3 same ((rectangular or rectangle or square) with (substrate\$1 or wafer\$1))	USPAT; US-PGPUB;	2002/09/25 16:57
		,	EPO; JPO; DERWENT; IBM_TDB	
15	366	(etch\$3 same ((rectangular or rectangle or square) with (substrate\$1 or wafer\$1))) and ((uniformity or uniform) with etch\$3)	USPAT; US-PGPUB;	2002/09/25 16:58
			EPO; JPO; DERWENT;	
22	70	((etch\$3 same ((rectangular or rectangle or square) with (substrate\$1 or wafer\$1))) and ((uniformity or uniform) with etch\$3)) and ((second adj4 power) or (second adj4	IBM_TDB USPAT; US-PGPUB;	2002/09/25 17:00
		electrode))	EPO; JPO; DERWENT; IBM_TDB	